

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

April 23, 2004

(Use several sheets if necessary)

ATTORNEY DOCKET NO.
3194.1022-002
(7184-PA13C)APPLICATION NO.
10/692,018FIRST NAMED INVENTOR
Daniel Alvarez, Jr.FILING DATE
October 23, 2003

EXAMINER

CONFIRMATION NO.
8519GROUP
1724

U.S. PATENT DOCUMENTS

EXAM- INER INITIAL	REF. NO.	DOCUMENT NUMBER Number-Kind Code (if known)	ISSUE DATE / PUBLICATION DATE MM-DD-YYYY	NAME OF PATENTEE OR APPLICANT OF CITED DOCUMENT
HL	AA	5,685,895	11-11-1997	Hagiwara <i>et al.</i>
	AB	5,910,292	6-8-1999	Alvarez, Jr. <i>et al.</i>
	AC	6,059,859	5-9-2000	Alvarez, Jr. <i>et al.</i>
	AD	6,103,206	8-15-2000	Taylor, Jr. <i>et al.</i>
	AE	4,855,276	8-8-1989	Osborne <i>et al.</i>
	AF	5,607,647	3-4-1997	Kinthead
	AG	4,663,300	5-5-1987	Lester <i>et al.</i>
	AH	4,735,927	4-5-1988	Gerdes <i>et al.</i>
	AI	4,798,813	1-17-1989	Kato <i>et al.</i>
	AJ	4,869,735	9-26-1989	Miyazawa <i>et al.</i>
	AK	5,171,422	12-15-1992	Kirker <i>et al.</i>
	AA2	5,328,672	7-12-1994	Montreuil <i>et al.</i>
	AB2	5,430,000	7-4-1995	Timken
	AC2	6,114,268	9-5-2000	Wu <i>et al.</i>
	AD2	6,569,394 B2	5-27-2003	Fischer <i>et al.</i>
	AE2	6,576,587 B2	6-10-2003	Labarge <i>et al.</i>
	AF2	6,645,898 B2	11-11-2003	Alvarez, Jr. <i>et al.</i>
HL	AG2	6,391,090 B1	5-21-2002	Alvarez, Jr. <i>et al.</i>
	AH2			
	AI2			
	AJ2			
	AK2			
	AA3			
	AB3			
	AC3			

EXAMINER

Frank Lawrence

DATE CONSIDERED

11-9-04

PTO-1349 REPRODUCED INFORMATION DISCLOSURE CITATION IN AN APPLICATION April 23, 2004 (Use several sheets if necessary)	ATTORNEY DOCKET NO. 3194.1022-002 (7184-PA13C)		APPLICATION NO. 10/692,018	
	FIRST NAMED INVENTOR Daniel Alvarez, Jr.		FILING DATE October 23, 2003	
	EXAMINER		CONFIRMATION NO. 8519	GROUP 1724

FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER Country Code-Number-Kind Code (if known)	DATE MM-DD-YYYY	NAME OF PATENTEE OR APPLICANT OF CITED DOCUMENT	TRANSLATION YES NO	
72	AL	WO 88/02659	04-21-1988	Steuler-Industriewerke GmbH	X	
	AM					
	AN					
	AO					
	AP					
	AQ					
	AL2					
	AM2					
	AN2					
	AO2					
	AP2					
	AQ2					
	AL3					
	AM3					
	AN3					
	AO3					
	AP3					
	AQ3					
	AL4					
	AM4					
	AN4					
	AO4					
	AP4					
	AQ4					

EXAMINER <i>Frank Lawrence</i>	DATE CONSIDERED 11-9-04
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PTO-1449 REPRODUCED INFORMATION DISCLOSURE CITATION IN AN APPLICATION April 23, 2004 (Use several sheets if necessary)	ATTORNEY DOCKET NO. 3194.1022-002 (7184-PA13C)		APPLICATION NO. 10/692,018	
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	EXAMINER	CONFIRMATION NO. 8519	GROUP 1724	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
AR	AL	Dallas, Andrew J., <i>et al.</i> , "Protecting the DUV Process and Optimizing Optical Transmission", <i>Meterology, Inspection, and Process Control for Microlithography XIV</i> , Neal T. Sullivan, Editor, Proceedings of SPIE, Vol. 3998, pages 863-74 (2000).
AS	FL	Holmes, S. J., <i>et al.</i> , "Manufacturing with DUV Lithography", <i>IBM Journal of Research and Development</i> , Vol. 41, Optical Lithography (1997).
AT	JR	Kishkovich, Oleg, <i>et al.</i> , "Real-Time Methodologies for Monitoring Airborne Molecular Contamination in Modern DUV Photolithography Facilities", <i>SPIE Conference on Meterology, Inspection, and Process Control in Microlithography XIII</i> , Vol. 3677, pages 348-76 (March 1999).
AU	JR	Koshkovich, Oleg, <i>et al.</i> , "An Accelerated Testing Technique for Evaluating Performance of Chemical Air Filters for DUV Photolithographic Equipment", <i>SPIE Conference on Meterology, Inspection, and Process Control in Microlithography XIII</i> , Vol. 3677, pages 857-65 (March 1999).
AV	JL	MacDonald, Scott A., <i>et al.</i> , "Airborne Contamination of a Chemically Amplified Resist 1 Identification of Problem", <i>Chem. Mater</i> , Vol. 5, pages 348-56 (1993).
AW	JL	Zhu, Sheng-Bai, "Contamination Control During Sh8pp8ng, Handling and Storage of Reticles", <i>Meterology, Inspection, and Process Control for Microlithography XIV</i> , Neal T. Sullivan, Editor, Proceedings of SPIE, Vol. 3998, pages 565-72 (2000).
AX	JL	<i>Ullmans' Encyclopedia of Industrial Chemistry, Completely Revised Fifth Edition</i> , Editors Barbara Elvers and Stephen Hawkins, Vol. 28A, pages 475-90 (1985).
AY	JL	<i>Kirk-Othmer Encyclopedia of Chemical Technology, Third Edition</i> , Vol. 15, pages 639-55, 1339-69 (1978).
AZ		
AR2		
AS2		
AT2		

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